

AZ 9260 – run sheet

MicroChemicals GmbH / Merck KGaA (AZ brand; originally launched by Clariant / AZ Electronic Materials)

nanyte.com/photoresists/az-9260 · last updated 2026-07-26

Thickness: 7.9–11.4 µm

Softbake: 110 °C · 2.8 min · hotplate

Exposure dose: 1500 mJ/cm²

Develop: Developer AZ 400K Developer (buffered, KOH-based) · Dilution 1:4 · Time 3 min · Rinse 300 rpm spin rinse for 20 s, then 4000 rpm spin-dry for 15 s (from the 10 um single-coat 'Typical Process') · Method spray, dispense temperature 27 C (immersion is also usable per current MicroChemicals guidance)